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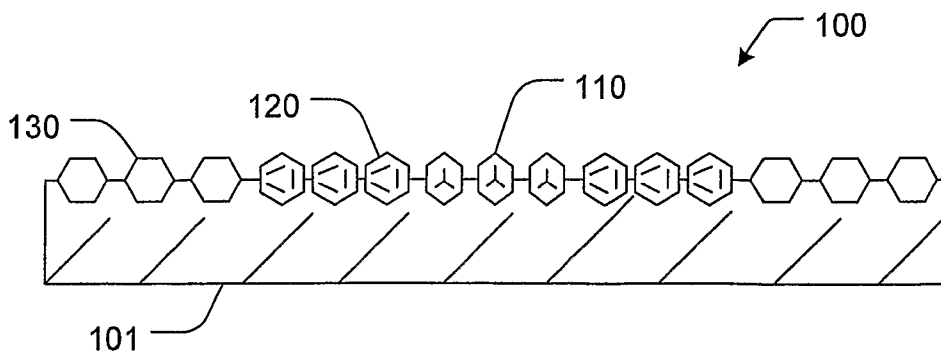
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(54) Title: CMP PADE DRESSER WITH ORIENTED PARTICLES AND ASSOCIATED METHODS



(57) Abstract: CMP pad dressers (100) with superabrasive particles (130, 120, 110) oriented into an attitude that controls CMP pad performance, and methods associated therewith are disclosed and described. The controlled CMP pad performance may be selected to optimize CMP pad dressing rate and dresser wear.



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